



# **STIC Search Report**

## **EIC 1700**

**STIC Database Tracking Number: 145756**

**TO: Sanza McClendon**  
**Location: REM 10D70**  
**Art Unit : 1711**  
**March 3, 2005**

**Case Serial Number: 10712590**

**From: Usha Shrestha**  
**Location: EIC 1700**  
**REMSSEN 4B28**  
**Phone: 571/272-3519**  
**usha.shrestha@uspto.gov**

### **Search Notes**



# STIC Search Results Feedback Form

**EIC17000**

Questions about the scope or the results of the search? Contact *the EIC searcher or contact:*

Kathleen Fuller, EIC 1700 Team Leader  
571/272-2505 REMSEN 4B28

## Voluntary Results Feedback Form

- I am an examiner in Workgroup:  Example: 1713  
➤ Relevant prior art **found**, search results used as follows:

- ☐ 102 rejection
- ☐ 103 rejection
- ☐ Cited as being of interest.
- ☐ Helped examiner better understand the invention.
- ☐ Helped examiner better understand the state of the art in their technology.

Types of relevant prior art found:

- ☐ Foreign Patent(s)
- ☐ Non-Patent Literature  
(journal articles, conference proceedings, new product announcements etc.)

➤ Relevant prior art **not found**:

- ☐ Results verified the lack of relevant prior art (helped determine patentability).
- ☐ Results were not useful in determining patentability or understanding the invention.

Comments:

Drop off or send completed forms to EIC1700 REMSEN 4B28

Mellerson, Kendra

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From: Unknown@Unknown.com  
Sent: Tuesday, February 22, 2005 2:28 PM  
To: STIC-EIC1700  
Subject: Generic form response

ResponseHeader=Commercial Database Search Request

AccessDB#= 145756

LogNumber= \_\_\_\_\_

Searcher= \_\_\_\_\_

SearcherPhone= \_\_\_\_\_

SearcherBranch= \_\_\_\_\_

MyDate=Tue Feb 22 14:27:00 GMT-0500 (Eastern Standard Time) 2005

submitto=STIC-EIC1700@uspto.gov

Name=Sanza McClendon

Empno=75688

Phone=2-1074

Artunit=1711

Office=10D70 Rem

Serialnum=10/712,590

PatClass=522/187

Earliest=11/13/2003

Format1=paper

Searchtopic=please search for the process of claim 1

Comments=

send=SEND

SCIENTIFIC REFERENCE BR  
Sci & Tech Inf - Cnt  
FEB 22 2005

SCIENTIFIC REFERENCE BR  
Sci & Tech Inf - Cnt  
FEB 22 2005

Pat. & T.M. Office



## UNITED STATES PATENT AND TRADEMARK OFFICE

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## \*BIBDATASHEET\*

CONFIRMATION NO. 8997

Bib Data Sheet

SERIAL NUMBER 10/712,590	FILING DATE 11/13/2003  RULE	CLASS 522	GROUP ART UNIT 1711	ATTORNEY DOCKET NO. 59390US002
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APPLICANTS

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 Klaus Hintzer, Kastl, GERMANY; Arne Thaler, Altoetting, GERMANY;  
 Tatsuo Fukushi, Woodbury, MN;  
 Naiyong Jing, Woodbury, MN;  
 Kai Helmut Lochhaas, Neuoeetting, GERMANY;

\*\* CONTINUING DATA \*\*\*\*\*

\*\* FOREIGN APPLICATIONS \*\*\*\*\*

IF REQUIRED, FOREIGN FILING LICENSE GRANTED  
 \*\* 02/10/2004

Foreign Priority claimed 35 USC 119 (a-d) conditions met	<input type="checkbox"/> yes <input type="checkbox"/> no  <input type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> Met after Allowance	STATE OR COUNTRY MN	SHEETS DRAWING 2	TOTAL CLAIMS 58	INDEPENDENT CLAIMS 1
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Verified and Acknowledged  
 Examiner's Signature \_\_\_\_\_ Initials \_\_\_\_\_

ADDRESS  
 32692  
 3M INNOVATIVE PROPERTIES COMPANY  
 PO BOX 33427  
 ST. PAUL , MN  
 55133-3427

TITLE  
 Bromine, chlorine or iodine functional polymer electrolytes crosslinked by e-beam

FILING FEE	FEES: Authority has been given in Paper	<input type="checkbox"/> All Fees
		<input type="checkbox"/> 1.16 Fees ( Filing )

<p>RECEIVED 1584</p>	<p>No. _____ to charge/credit DEPOSIT ACCOUNT</p>	<p><input type="checkbox"/> 1.17 Fees ( Processing Ext. of time )</p>
	<p>No. _____ for following:</p>	<p><input type="checkbox"/> 1.18 Fees ( Issue )</p>
		<p><input type="checkbox"/> Other _____</p>
		<p><input type="checkbox"/> Credit</p>

**Bromine, Chlorine or Iodine Functional Polymer Electrolytes  
Crosslinked by E-Beam**

**Abstract**

5           A method is provided for making a crosslinked polymer electrolyte, typically in  
the form of a membrane for use as a polymer electrolyte membrane in an electrolytic  
cell such as a fuel cell, as well as the polymer so made, the method comprising  
application of electron beam radiation to a highly fluorinated fluoropolymer  
comprising: a backbone derived in part from tetrafluoro-ethylene monomer, first  
10   pendent groups which include a group according to the formula  $-\text{SO}_2\text{X}$ , where X is F,  
Cl, Br, OH or  $-\text{O}^-\text{M}^+$ , where  $\text{M}^+$  is a monovalent cation, and second pendent groups  
which include Br, Cl or I. Typically, the membrane has a thickness of 90 microns or  
less, more typically 60 or less, and most typically 30 microns or less.

We claim:

1. A method of making a crosslinked polymer comprising the steps of:
  - a) providing a highly fluorinated fluoropolymer comprising: a backbone derived in part from tetrafluoroethylene monomer, first pendent groups which include a group according to the formula  $-\text{SO}_2\text{X}$ , where X is F, Cl, Br, OH or  $-\text{O}-\text{M}^+$ , where  $\text{M}^+$  is a monovalent cation, and second pendent groups which include a halogen atom selected from the group consisting of Br, Cl and I; and
  - b) exposing said fluoropolymer to electron beam radiation so as to result in the formation of crosslinks.
2. The method according to claim 1 wherein said method additionally comprises, prior to said step b), the step of:
  - c) forming said fluoropolymer into a membrane.
3. The method according to claim 1 wherein said membrane has a thickness of 90 microns or less.
4. The method according to claim 1 wherein said step of exposing said fluoropolymer to electron beam radiation comprises exposing said fluoropolymer to greater than 1 Mrad of electron beam radiation.
5. The method according to claim 1 wherein said step of exposing said fluoropolymer to electron beam radiation comprises exposing said fluoropolymer to greater than 3 Mrad of electron beam radiation.
6. The method according to claim 1 wherein said step of exposing said fluoropolymer to electron beam radiation comprises exposing said fluoropolymer to greater than 15 Mrad of electron beam radiation.
7. The method according to claim 1 wherein said highly fluorinated fluoropolymer is perfluorinated.

8. The method according to claim 1 wherein said pendent groups are according to the formula  $-R^1-SO_2X$ , where  $R^1$  is a branched or unbranched perfluoroalkyl or perfluoroether group comprising 1-15 carbon atoms and 0-4 oxygen atoms, and where  
5 X is F, Cl, Br, OH or  $-O^-M^+$ , where  $M^+$  is a monovalent cation.
9. The method according to claim 1 wherein said pendent groups are groups according to the formula  $-O-(CF_2)_4-SO_2X$ , where X is F, Cl, Br, OH or  $-O^-M^+$ , where  
10  $M^+$  is a monovalent cation.
10. The method according to claim 1 wherein said pendent groups are groups according to the formula  $-O-(CF_2)_4-SO_3H$ .
11. The method according to claim 1 wherein said halogen atom included in said  
15 second pendent groups is Br.
12. The method according to claim 8 wherein said halogen atom included in said second pendent groups is Br.
- 20 13. The method according to claim 2 wherein said pendent groups are according to the formula  $-R^1-SO_2X$ , where  $R^1$  is a branched or unbranched perfluoroalkyl or perfluoroether group comprising 1-15 carbon atoms and 0-4 oxygen atoms, and where X is F, Cl, Br, OH or  $-O^-M^+$ , where  $M^+$  is a monovalent cation.
- 25 14. The method according to claim 2 wherein said pendent groups are groups according to the formula  $-O-(CF_2)_4-SO_2X$ , where X is F, Cl, Br, OH or  $-O^-M^+$ , where  $M^+$  is a monovalent cation.



15. The method according to claim 2 wherein said pendent groups are groups according to the formula  $-\text{O}-(\text{CF}_2)_4-\text{SO}_3\text{H}$ .
16. The method according to claim 2 wherein said halogen atom included in said  
5 second pendent groups is Br.
17. The method according to claim 3 wherein said halogen atom included in said second pendent groups is Br.
- 10 18. The method according to claim 3 wherein said pendent groups are according to the formula  $-\text{R}^1-\text{SO}_2\text{X}$ , where  $\text{R}^1$  is a branched or unbranched perfluoroalkyl or perfluoroether group comprising 1-15 carbon atoms and 0-4 oxygen atoms, and where X is F, Cl, Br, OH or  $-\text{O}^-\text{M}^+$ , where  $\text{M}^+$  is a monovalent cation.
- 15 19. The method according to claim 3 wherein said pendent groups are groups according to the formula  $-\text{O}-(\text{CF}_2)_4-\text{SO}_2\text{X}$ , where X is F, Cl, Br, OH or  $-\text{O}^-\text{M}^+$ , where  $\text{M}^+$  is a monovalent cation.
- 20 20. The method according to claim 3 wherein said pendent groups are groups according to the formula  $-\text{O}-(\text{CF}_2)_4-\text{SO}_3\text{H}$ .
21. The method according to claim 3 wherein said halogen atom included in said second pendent groups is Br.
- 25 22. The method according to claim 18 wherein said halogen atom included in said second pendent groups is Br.
23. The method according to claim 4 wherein said pendent groups are according to the formula  $-\text{R}^1-\text{SO}_2\text{X}$ , where  $\text{R}^1$  is a branched or unbranched perfluoroalkyl or

perfluoroether group comprising 1-15 carbon atoms and 0-4 oxygen atoms, and where X is F, Cl, Br, OH or  $-O-M^+$ , where  $M^+$  is a monovalent cation.

24. The method according to claim 4 wherein said pendent groups are groups  
5 according to the formula  $-O-(CF_2)_4-SO_2X$ , where X is F, Cl, Br, OH or  $-O-M^+$ , where  $M^+$  is a monovalent cation.

25. The method according to claim 4 wherein said pendent groups are groups  
10 according to the formula  $-O-(CF_2)_4-SO_3H$ .

26. The method according to claim 4 wherein said halogen atom included in said  
second pendent groups is Br.

27. The method according to claim 23 wherein said halogen atom included in said  
15 second pendent groups is Br.

28. The method according to claim 1 wherein step c) comprises imbibing said  
fluoropolymer into a porous supporting matrix.

20 29. The method according to claim 28 wherein said porous supporting matrix is a  
porous polytetrafluoroethylene web.

30. A polymer electrolyte membrane comprising the crosslinked polymer made  
according to the method of claim 1.

25 31. A polymer electrolyte membrane comprising the crosslinked polymer made  
according to the method of claim 2.

30 32. A polymer electrolyte membrane comprising the crosslinked polymer made  
according to the method of claim 3.

33. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 4.
34. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 5.
35. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 6.
36. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 7.
37. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 8.
38. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 9.
39. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 10.
40. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 11.
41. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 12.
42. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 13.

43. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 14.
44. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 15.
45. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 16.
46. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 17.
47. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 18.
48. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 19.
49. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 20.
50. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 21.
51. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 22.
52. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 23.

53. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 24.
54. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 25.
55. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 26.
56. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 27.
57. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 28.
58. A polymer electrolyte membrane comprising the crosslinked polymer made according to the method of claim 29.

=> fil reg

FILE 'REGISTRY' ENTERED AT 14:42:19 ON 03 MAR 2005  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
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FILE 'LREGISTRY' ENTERED AT 11:45:29 ON 03 MAR 2005  
L1 STR

FILE 'REGISTRY' ENTERED AT 11:50:05 ON 03 MAR 2005  
L2 50 S L1  
L3 SCR 2043  
L4 50 S L1 AND L3  
L5 1051 S L1 AND L3 FUL  
SAV L5 MCC590/A

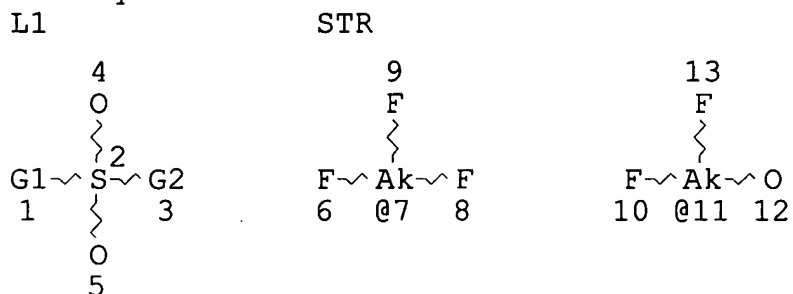
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L8 2068 S L5  
L9 556 S L8(L)PREP/RL  
L10 352 S L9 AND (POLYMER? OR PLASTIC?)/SC  
L11 2 S L10 AND (ELECTRON(A)BEAM? OR E(A)BEAM?)  
L12 40 S L10 AND FUEL(2A)CELL?  
L13 40 S L10 AND CROSSLINK?  
L14 11 S L13 AND FUEL(2A)CELL?  
L15 41 S L14 OR L12 OR L11  
L16 20 S L10 AND IODI?  
L17 2 S L16 AND (SECOND? OR TWO? OR DOUBLE?)  
L18 1 S L15 AND (SECOND? OR TWO? OR DOUBLE?)  
L19 31 S L10 AND MEMBRAN?(3A)ELECTROLY?  
L20 12 S L19 AND FUEL(2A)CELL?  
L21 15 S L10 AND MEMBRAN?(3A)ELECTROLY?(2A)CELL?  
L22 19 S L20 OR L21  
L23 48 S L22 OR L15

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L24 24 S L5 AND 1-3/I

FILE 'HCAPLUS' ENTERED AT 13:35:44 ON 03 MAR 2005  
L25 8 S L24  
L26 1 S L25 AND MEMBRAN?  
L27 11 S L25 OR L17 OR L18  
L28 1 S L27 AND FUEL(A)CELL?  
L29 1 S L27 AND ELECTROLY?(2A)CELL?  
L30 2 S L26 OR L28 OR L29  
L31 47 S L23 NOT L27

FILE 'REGISTRY' ENTERED AT 14:42:19 ON 03 MAR 2005

=&gt; d que 18



VAR G1=7/11

VAR G2=F/CL/BR/OH

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DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

NUMBER OF NODES IS 13

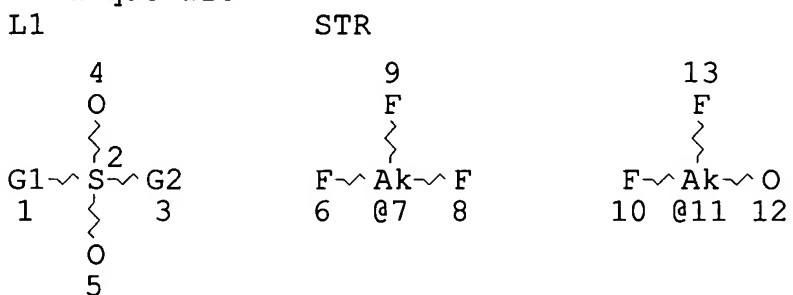
STEREO ATTRIBUTES: NONE

L3 SCR 2043

L5 1051 SEA FILE=REGISTRY SSS FUL L1 AND L3

L8 2068 SEA FILE=HCAPLUS ABB=ON PLU=ON L5

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VAR G1=7/11

VAR G2=F/CL/BR/OH

NODE ATTRIBUTES:

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

NUMBER OF NODES IS 13

STEREO ATTRIBUTES: NONE

L3 SCR 2043

L5 1051 SEA FILE=REGISTRY SSS FUL L1 AND L3

L24 24 SEA FILE=REGISTRY ABB=ON PLU=ON L5 AND 1-3/I

L25 8 SEA FILE=HCAPLUS ABB=ON PLU=ON L24

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YOU HAVE REQUESTED DATA FROM FILE 'HCAPLUS' - CONTINUE? (Y)/N:n

=> fil hcaplus

FILE 'HCAPLUS' ENTERED AT 14:44:17 ON 03 MAR 2005

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L27 ANSWER 1 OF 11 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2003:132104 HCAPLUS

DOCUMENT NUMBER: 139:36909

TITLE: Amplified quenching in metal-organic  
conjugated polymers

AUTHOR(S): Liu, Yao; Jiang, Shujun; Schanze, Kirk S.

CORPORATE SOURCE: Department of Chemistry, University of  
Florida, Gainesville, FL, USA

SOURCE: Chemical Communications (Cambridge, United  
Kingdom) (2003), (5), 650-651

CODEN: CHCOFS; ISSN: 1359-7345

PUBLISHER: Royal Society of Chemistry

DOCUMENT TYPE: Journal

LANGUAGE: English

AB The luminescence from conjugated polyelectrolytes (CPE)s that contain pendant metal complex units is quenched efficiently by oppositely charged electron acceptors. The polyacetylenes having pendant Ru or Os ligand complex chains and model compds. were prepared by Sonogashira coupling reactions and fully characterized by NMR and mass spectrometry (for the models). Amplified quenching occurs in the conjugated polymers where the lowest excited state has triplet spin character and data suggests that diffusion of the  $3\pi, \pi^*$  state along the PPE backbone is not kinetically competitive with alternate pathways for quenching, including self-exchange exciton hopping and/or directed diffusion of the quencher along the polyelectrolyte chain. Comparison of



these results with those obtained on fluorescent CPEs, where amplified quenching involves a singlet exciton, hints that diffusion of the triplet exciton is slow.

IT **540470-79-9P**

(preparation of monomers and Ru- and Os-butoxy-bipyridyl side chain poly(phenylacetylene) conjugated polyelectrolytes and mechanism of luminescence quenching by electron acceptors)

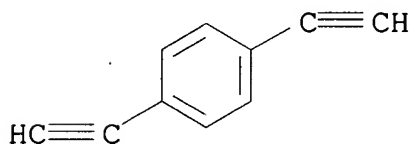
RN 540470-79-9 HCAPLUS

CN Ruthenium(2+), bis(2,2'-bipyridine- $\kappa$ N1, $\kappa$ N1') [4-[4-[4-(heptyloxy)-2,5-diiodophenoxy]butyl]-4'-methyl-2,2'-bipyridine- $\kappa$ N1, $\kappa$ N1']-, (OC-6-33)-, salt with trifluoromethanesulfonic acid (1:2), polymer with 1,4-diethynylbenzene (9CI) (CA INDEX NAME)

CM 1

CRN 935-14-8

CMF C10 H6



CM 2

CRN 540470-70-0

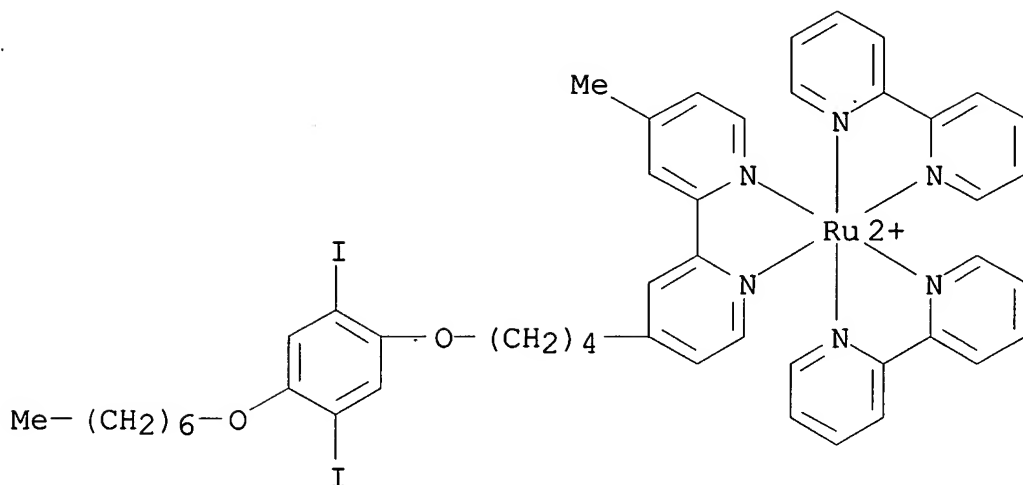
CMF C48 H50 I2 N6 O2 Ru . 2 C F3 O3 S

CM 3

CRN 540470-69-7

CMF C48 H50 I2 N6 O2 Ru

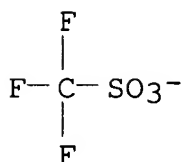
CCI CCS



CM 4

CRN 37181-39-8

CMF C F3 O3 S



CC 35-7 (Chemistry of Synthetic High Polymers)

Section cross-reference(s): 36, 73

IT 540470-48-2P 540470-60-8P **540470-79-9P** 540470-80-2P

(preparation of monomers and Ru- and Os-butoxy-bipyridyl side chain poly(phenylacetylene) conjugated polyelectrolytes and mechanism of luminescence quenching by electron acceptors)

REFERENCE COUNT: 15 THERE ARE 15 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L27 ANSWER 2 OF 11 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2002:957151 HCAPLUS

DOCUMENT NUMBER: 138:311425

TITLE: Acid catalyst mobility in resist resins

AUTHOR(S): Stewart, Michael D.; Tran, Hoang Vi; Schmid, Gerard M.; Stachowiak, Timothy B.; Becker, Darren J.; Willson, C. Grant

CORPORATE SOURCE: Department of Chemical Engineering, The University of Texas at Austin, Austin, TX, 78712, USA

SOURCE: Journal of Vacuum Science & Technology, B: Microelectronics and Nanometer Structures (2002), 20(6), 2946-2952  
CODEN: JVTBD9; ISSN: 0734-211X

PUBLISHER: American Institute of Physics

DOCUMENT TYPE: Journal

LANGUAGE: English

AB In a chemical amplified resist absorbed photons generate stable catalyst mols. instead of directly switching resist solubility via photochem. reaction. This allows for much lower exposure doses to be used in imaging. Some catalyst mobility is necessary to achieve amplification since the catalyst must move from reaction site to reaction site, but a mobile catalyst can blur the deposited aerial image. Catalyst mols. that are free to move in exposed regions are also free to move into adjacent unexposed regions. Understanding acid catalyst diffusion in photoresist resins is complicated by the constantly changing chemical environment the diffusing catalyst experiences as the resist undergoes chemical reactions. The diffusing catalyst promotes chemical reactions which change the properties of its surrounding resin. In addition, it is possible a transient material state is generated by volatile reaction byproducts and their desorption from the film. In most photoresist systems it is impossible to sep. reaction and diffusion effects. This work describes studies of acid diffusion in polymers that are close structural analogs to reactive photoresist resins but do not react with the diffusing acidic catalyst. The purpose of this study into nonreactive polymer is to gain insight into the more complex, reactive systems. In addition, expts. with polymeric photoacid generators are reported. These materials provide added insight into acid transport in photoresist materials.

IT **509100-87-2**

(polymeric photoacid generator; diffusion of acid mols. in polymers in relation to mobility of photogenerated acid in chemical amplified photoresists)

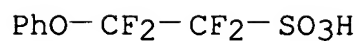
RN 509100-87-2 HCAPLUS

CN Ethanesulfonic acid, 1,1,2,2-tetrafluoro-2-phenoxy-, compd. with ethenylbenzene polymer with 1-ethenyl-4-(methylthio)benzene, and iodomethane (9CI) (CA INDEX NAME)

CM 1

CRN 509100-86-1

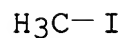
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CM 2

CRN 74-88-4

CMF C H3 I



CM 3

CRN 29324-56-9

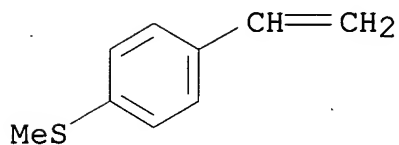
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CCI PMS

CM 4

CRN 18760-11-7

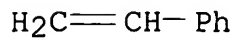
CMF C9 H10 S



CM 5

CRN 100-42-5

CMF C8 H8



CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and

Other Reprographic Processes)

IT 252975-70-5D, dimethylphenylsulfonium ion exchange

**509100-87-2**

(polymeric photoacid generator; diffusion of acid mols. in polymers in relation to mobility of photogenerated acid in chemical amplified photoresists)

REFERENCE COUNT: 15 THERE ARE 15 CITED REFERENCES AVAILABLE  
FOR THIS RECORD. ALL CITATIONS AVAILABLE  
IN THE RE FORMAT

L27 ANSWER 3 OF 11 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2000:628185 HCAPLUS

DOCUMENT NUMBER: 133:223513

TITLE: Fluorinated copolymers from preemulsified  
comonomers and method for free radical  
polymerization thereof

INVENTOR(S): Bekiarian, Paul Gregory; Farnham, William  
Brown

PATENT ASSIGNEE(S): E. I. Du Pont de Nemours &amp; Co., USA

SOURCE: PCT Int. Appl., 21 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2000052060	A1	20000908	WO 2000-US5526	2000 0302
W: AU, CA, CN, FI, JP, KR, MX, US RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
CA 2362289	AA	20000908	CA 2000-2362289	2000 0302
EP 1165624	A1	20020102	EP 2000-913714	2000 0302
EP 1165624	B1	20041208		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, FI				
JP 2002538235	T2	20021112	JP 2000-602283	2000 0302
AT 284418	E	20041215	AT 2000-913714	

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2000  
0302

AB The method comprises copolymerizing in aqueous emulsion one or more monomers selected from tetrafluoroethylene (TFE), trifluoroethylene, vinylidene fluoride, vinyl fluoride, ethylene, chlorotrifluoroethylene, hexafluoropropylene, perfluoromethyl vinyl ether, and perfluoroethyl vinyl ether with a fluorinated comonomer having limited water solubility, in the presence of a fluorinated surfactant and free-radical initiator. The comonomer is dispersed in the form of droplets of  $\leq 10 \mu$  size and preferably is perfluorosulfonate ethoxypropyl vinyl ether (PSEPVE). The copolymer preferably is hydrolyzed using a basic solution to provide the alkali metal cationic form of the ionomer, and can be melt processed into a film or sheet. The copolymers having certain ionic conductivity, water swelling and effective ionic concentration, are useful in electrochem. applications such as lithium batteries, polymer electrolyte membrane **fuel cells**, electrolysis **cells**, ion-exchange membranes, sensors, electrochem. capacitors, and modified electrodes, and strong acid catalysts (no data). Thus, 150 g PSEPVE aqueous emulsion, 13.2 g ammonium perfluorooctanoate, and 0.9 g potassium persulfate solution in 20 mL water was polymerized under 200 psi TFE at 60° for 1.23 h to obtain a clear, water-white latex containing 16% polymer solids, which was frozen, defrosted, washed and dried to yield 320 g fine polymer powder. The above polymer was melt pressed at 320° and 5 klb pressure to obtain a clear film (2.5-3.5 mil) which was hydrolyzed in a 0.5 M solution of LiOH in 1:2 DMSO:H<sub>2</sub>O at 70° for 4 h, washed, acid-exchanged in 1.0 M nitric, and washed to obtain a membrane having water uptake 15 weight% and ionic conductivity at 23° 65 mS/cm.

IT **62879-78-1DP**, hydrolyzed **62879-78-1P**  
**291750-38-4P 291750-39-5P**  
(fluoropolymers from preemulsified comonomers and free-radical polymerization thereof)

RN 62879-78-1 HCAPLUS

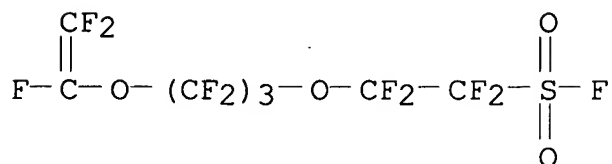
CN Ethanesulfonyl fluoride, 1,1,2,2-tetrafluoro-2-[1,1,2,2,3,3-

hexafluoro-3-[(trifluoroethenyl)oxy]propoxy]-, polymer with tetrafluoroethene (9CI) (CA INDEX NAME)

CM 1

CRN 62879-77-0

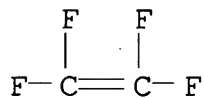
CMF C7 F14 O4 S



- CM 2

CRN 116-14-3

CMF C2 F4



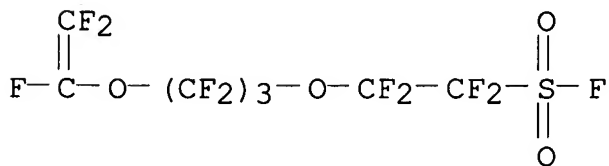
RN 62879-78-1 HCAPLUS

CN Ethanesulfonyl fluoride, 1,1,2,2-tetrafluoro-2-[1,1,2,2,3,3-hexafluoro-3-[(trifluoroethenyl)oxy]propoxy]-, polymer with tetrafluoroethene (9CI) (CA INDEX NAME)

CM 1

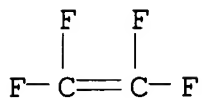
CRN 62879-77-0

CMF C7 F14 O4 S



CM 2

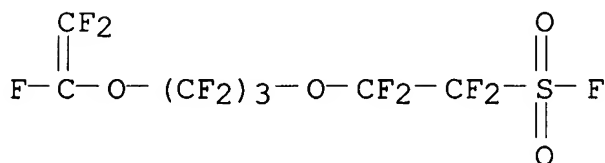
CRN 116-14-3  
CMF C2 F4



RN 291750-38-4 HCAPLUS  
CN Ethanesulfonyl fluoride, 1,1,2,2-tetrafluoro-2-[1,1,2,2,3,3-hexafluoro-3-[(trifluoroethenyl)oxy]propoxy]-, polymer with 1,1-difluoroethene (9CI) (CA INDEX NAME)

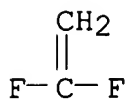
CM 1

CRN 62879-77-0  
CMF C7 F14 O4 S



CM 2

CRN 75-38-7  
CMF C2 H2 F2



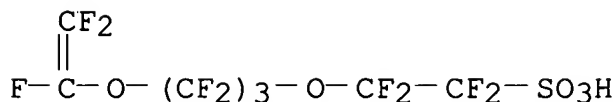
RN 291750-39-5 HCAPLUS  
CN Ethanesulfonic acid, 1,1,2,2-tetrafluoro-2-[1,1,2,2,3,3-hexafluoro-3-[(trifluoroethenyl)oxy]propoxy]-, lithium salt, polymer with 1,1-difluoroethene (9CI) (CA INDEX NAME)

CM 1

CRN 97008-86-1



CMF C7 H F13 O5 S . Li

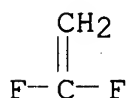


● Li

CM 2

CRN 75-38-7

CMF C2 H2 F2



- IC ICM C08F002-18  
ICS C08F214-22; C08F214-26
- CC 37-3 (**Plastics** Manufacture and Processing)  
Section cross-reference(s): 38, 52, 72, 76
- ST perfluorosulfonate ethoxypropyl vinyl ether copolymer prepn;  
tetrafluoroethylene preemulsified comonomer polymn; ammonium  
perfluorooctanoate surfactant preemulsified comonomer polymn;  
electrolyte membrane **fuel cell** fluorinated  
copolymer; ion exchange membrane ionic fluoropolymer; sensor  
perfluoro vinyl ether tetrafluoroethylene copolymer; electrode  
modified ionic fluoropolymer; acid catalyst ionic fluoropolymer
- IT Chemically modified electrodes  
Electrolytic capacitors  
Electrolytic cells  
**Fuel cells**  
Ion exchange membranes  
(fluoropolymers from preemulsified comonomers and free-radical  
polymerization thereof)
- IT **Secondary** batteries  
(lithium; fluoropolymers from preemulsified comonomers and  
free-radical polymerization thereof)
- IT **62879-78-1DP**, hydrolyzed **62879-78-1P**  
**291750-38-4P 291750-39-5P**  
(fluoropolymers from preemulsified comonomers and free-radical

polymerization thereof)

REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE  
FOR THIS RECORD. ALL CITATIONS AVAILABLE  
IN THE RE FORMAT

L27 ANSWER 4 OF 11 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1999:342971 HCAPLUS

DOCUMENT NUMBER: 131:129715

TITLE: Oligomerization of (Diacetoxyiodo)benzene with  
Trifluoromethanesulfonic Acid. Preparation and  
Structure of Hypervalent Iodine Oligomers

AUTHOR(S): Kitamura, Tsugio; Wakimoto, Ichiro; Nakamura,  
Tetsu; Fujiwara, Yuzo

CORPORATE SOURCE: Department of Chemistry and Biochemistry  
Graduate School of Engineering, Kyushu  
University, Hakozaki Fukuoka, 812-8581, Japan

SOURCE: Organic Letters (1999), 1(2), 253-255

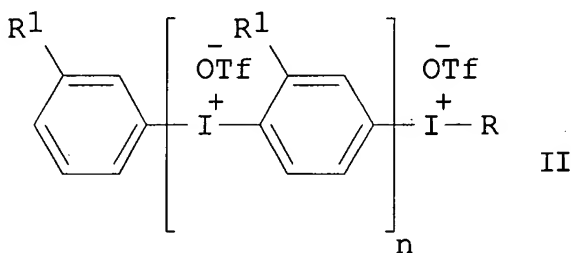
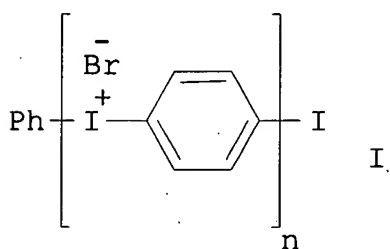
CODEN: ORLEF7; ISSN: 1523-7060

PUBLISHER: American Chemical Society

DOCUMENT TYPE: Journal

LANGUAGE: English

GI



AB Treatment of (diacetoxyiodo)benzene with an excess amount of trifluoromethanesulfonic acid (TfOH) gave hypervalent iodine oligomer I after quenching by aqueous NaBr. Thermolysis of I with KI yielded p-diiodobenzene and iodobenzene, indicating that I is an oligomer of para-substituted benzene rings connected through iodonium moieties. Iodine oligomers generated in situ react with benzene, toluene, and chlorobenzene to give the corresponding arylated iodine oligomers II (R = Ph, 4-MeC<sub>6</sub>H<sub>4</sub>, 4-ClC<sub>6</sub>H<sub>4</sub>; R<sub>1</sub> = H). Reaction of 3-MeC<sub>6</sub>H<sub>4</sub>I(OAc)<sub>2</sub> with triflic acid followed by quenching with NaBr gave the oligomer II (R = I; R<sub>1</sub> = Me) (no data); upon degradation with KI, II (R = I; R<sub>1</sub> = Me) gave 3-MeC<sub>6</sub>H<sub>4</sub>I

and 2,5-diiodotoluene, showing that polymerization occurs para to the iodonium moiety.

IT **234114-94-4DP**, reaction product with benzene  
 (oligomeric; preparation of arylated hypervalent iodine oligomers  
 by electrophilic regioselective polymerization of diacetoxyiodobenzene  
 and arylation with benzene, toluene, or chlorobenzene)

RN 234114-94-4 HCAPLUS

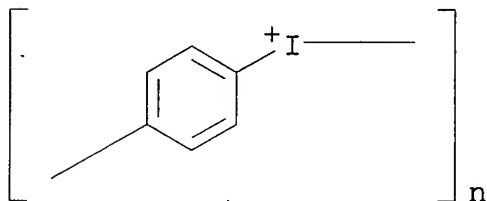
CN Poly[iodoniumylidene-1,4-phenylene salt with  
 trifluoromethanesulfonic acid (1:1)] (9CI) (CA INDEX NAME)

CM 1

CRN 234114-93-3

CMF (C6 H4 I)n

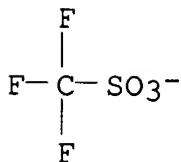
CCI PMS



CM 2

CRN 37181-39-8

CMF C F3 O3 S



(oligomeric; prepn. of hypervalent iodine oligomers by  
 electrophilic regioselective polymn. of diacetoxyiodobenzene)

IT **234114-94-4P**

(oligomeric; preparation of hypervalent iodine oligomers by  
 electrophilic regioselective polymerization of  
 diacetoxyiodobenzene)

RN 234114-94-4 HCAPLUS

CN Poly[iodoniumylidene-1,4-phenylene salt with

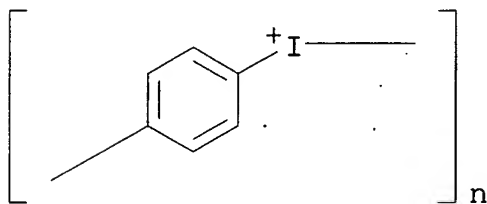
trifluoromethanesulfonic acid (1:1)] (9CI) (CA INDEX NAME)

CM 1

CRN 234114-93-3

CMF (C6 H4 I)n

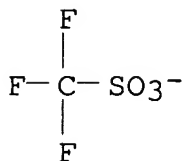
CCI PMS



CM 2

CRN 37181-39-8

CMF C F3 O3 S



IT **234778-70-2DP**, bromide-exchanged

(oligomeric; regiochem. of the preparation of hypervalent iodine oligomers by electrophilic polymerization of diacetoxyiodobenzene)

RN 234778-70-2 HCAPLUS

CN Poly[iodoniumylidene(methyl-1,4-phenylene) salt with trifluoromethanesulfonic acid (1:1)] (9CI) (CA INDEX NAME)

CM 1

CRN 234777-41-4

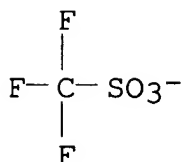
CMF (C7 H6 I)n

CCI IDS, PMS, MAN

\*\*\* STRUCTURE DIAGRAM IS NOT AVAILABLE \*\*\*

CM 2

CRN 37181-39-8  
CMF C F3 O3 S



CC 25-3 (Benzene, Its Derivatives, and Condensed Benzenoid Compounds)  
IT **234114-94-4DP**, reaction product with benzene  
**234114-94-4DP**, reaction product with chlorobenzene  
**234114-94-4DP**, reaction product with toluene  
(oligomeric; preparation of arylated hypervalent iodine oligomers  
by electrophilic regioselective polymerization of diacetoxyiodobenzene  
and arylation with benzene, toluene, or chlorobenzene)  
IT **234114-94-4DP**, bromide-exchanged  
(oligomeric; preparation of hypervalent iodine oligomers by  
electrophilic regioselective polymerization of  
diacetoxyiodobenzene)  
IT **234114-94-4P**  
(oligomeric; preparation of hypervalent iodine oligomers by  
electrophilic regioselective polymerization of  
diacetoxyiodobenzene)  
IT **234778-70-2DP**, bromide-exchanged  
(oligomeric; regiochem. of the preparation of hypervalent iodine  
oligomers by electrophilic polymerization of diacetoxyiodobenzene)  
REFERENCE COUNT: 24 THERE ARE 24 CITED REFERENCES AVAILABLE  
FOR THIS RECORD. ALL CITATIONS AVAILABLE  
IN THE RE FORMAT

L27 ANSWER 5 OF 11 HCAPLUS COPYRIGHT 2005 ACS on STN  
ACCESSION NUMBER: 1996:259816 HCAPLUS  
DOCUMENT NUMBER: 124:317967  
TITLE: Transformation of the Cationic Growing Center  
of Poly(tetrahydrofuran) into Samarium Amide.  
Block Copolymerization of Tetrahydrofuran with  
Methyl Methacrylate  
AUTHOR(S): Nomura, Ryoji; Narita, Mamiko; Endo, Takeshi  
CORPORATE SOURCE: Research Laboratory of Resources Utilization,  
Tokyo Institute of Technology, Yokohama, 226,  
Japan  
SOURCE: Macromolecules (1996), 29(11), 3669-73  
CODEN: MAMOBX; ISSN: 0024-9297  
PUBLISHER: American Chemical Society

DOCUMENT TYPE: Journal

LANGUAGE: English

AB **Two**-electron reduction of N-tert-butyl-N-methylaziridinium trifluoromethanesulfonate with samarium(II) **iodide** in the presence of hexamethylphosphoramide gave the corresponding samarium amides in an excellent yield through the reductive cleavage of a carbon-nitrogen bond of the ring followed by the elimination of ethylene. The produced samarium amide could polymerize Me methacrylate (MMA) in high initiation efficiency (80%), leading to the formation of highly syndiotactic poly(MMA) (85%) with narrow mol. weight distribution (<1.19). End capping of living poly(THF) with N-tert-butylaziridine and sequential reduction by samarium(II) **iodide** resulted in the corresponding poly(THF) with samarium amide moiety at the polymer end at functionality of 48%. The polymerization of MMA with the terminal samarium amide produced the block copolymer of THF with MMA.

IT **176259-77-1DP**, hydrolyzed or reaction product with benzoyl chloride  
(preparation and NMR characterization of aziridinium-terminated poly(THF) prepolymer for subsequent block polymerization with Me methacrylate)

RN 176259-77-1 HCAPLUS

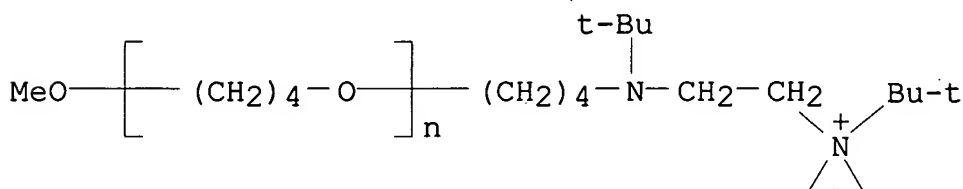
CN Poly(oxy-1,4-butanediyl),  $\alpha$ -[4-[(1,1-dimethylethyl)[2-[1-(1,1-dimethylethyl)aziridinio]ethyl]amino]butyl]- $\omega$ -methoxy-, salt with trifluoromethanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 176259-76-0

CMF (C4 H8 O)<sub>n</sub> C17 H37 N2 O

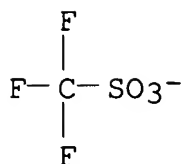
CCI PMS



CM 2

CRN 37181-39-8

CMF C F3 O3 S



- CC 35-3 (Chemistry of Synthetic High **Polymers**)
- ST polytetrahydrofuran growing center transformation samarium amide;  
samarium amide terminated polytetrahydrofuran polymn methacrylate;  
aziridinium redn samarium **iodide** catalyst prepn;  
methacrylate polymn samarium amide catalyst
- IT 49690-12-2P, N-tert-Butyl-N-methylbenzamide  
(model study; preparation by **two**-electron reduction of  
N-tert-butyl-N-methylaziridinium)
- IT 176259-79-3, N-tert-Butyl-N-methyl-methylaziridinium  
trifluoromethanesulfonate 176259-80-6, N-Benzyl-N-  
methylaziridinium trifluoromethanesulfonate 176259-82-8,  
N-Benzyl-N-methyl-methylaziridinium trifluoromethanesulfonate  
(model study; **two**-electron reduction with SmI2 of)
- IT **176259-77-1DP**, hydrolyzed or reaction product with benzoyl  
chloride  
(preparation and NMR characterization of aziridinium-terminated  
poly(THF) prepolymer for subsequent block polymerization with Me  
methacrylate).
- IT 32248-43-4, Samarium(II) **iodide**  
(**two**-electron reduction of N,N-dialkylaziridinium salts  
or N,N-dialkylaziridinium salt-terminated poly(THF) with)
- IT 680-31-9, Hexamethylphosphoramide, uses  
(**two**-electron reduction of N,N-dialkylaziridinium salts  
or N,N-dialkylaziridinium salt-terminated poly(THF) with SmI2  
in the presence of)
- IT 76343-13-0, N-tert-Butyl-N-methylaziridinium  
trifluoromethanesulfonate  
(**two**-electron reduction with SmI2 and application as a  
catalyst precursor in the polymerization of methacrylates)

L27 ANSWER 6 OF 11 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1995:499725 HCAPLUS

DOCUMENT NUMBER: 123:44388

TITLE: Silicon-containing sulfonium salts and  
photoresist compositions

INVENTOR(S): Iwasa, Shigeyuki; Nakano, Kaichiro; Maeda,  
Katsumi; Hasegawa, Etsuo

PATENT ASSIGNEE(S): Nippon Electric Co, Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 2  
 PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
JP 06342209	A2	19941213	JP 1993-204357	1993 0818
US 5747622	A	19980505	US 1997-797939	1997 0212
PRIORITY APPLN. INFO.:			JP 1993-78403	A 1993 0406
			JP 1993-204357	A 1993 0818
			JP 1993-329366	A 1993 1227
			US 1994-223767	B1 1994 0406

AB The salts contain p-ZO(C<sub>6</sub>H<sub>4</sub>-S+R<sub>1</sub>Y--C<sub>6</sub>H<sub>4</sub>-p-OX)<sub>n</sub>(R<sub>4</sub>OX)<sub>k</sub>Z [n = 10-700; k = 0, 1-700; n + k = 10-700; 1 k/n + k = 0-0.9; X = (SiR<sub>2</sub>R<sub>3</sub>)mO or (SiR<sub>2</sub>R<sub>3</sub>O)<sub>m</sub>-1SiR<sub>2</sub>R<sub>3</sub>O; m = 1-100; Y- = counter ion; Z = H, trimethylsilyl; R<sub>1</sub>-3 = Ph, C<sub>1</sub>-6 alkyl(-containing Ph); R<sub>4</sub> = C<sub>2</sub>-8 alkylene, phenylene]. The compns. contain the salts as acid generators.

IT **164580-15-8P 164580-22-7P 164580-23-8P**  
**164580-24-9P 164580-26-1P 329321-82-6P**  
**329321-85-9P 329322-05-6P 329322-16-9P**  
**329322-18-1P 329322-33-0P**

(photoresist compns. containing Si-containing polymer sulfonium salts as acid generators)

RN 164580-15-8 HCAPLUS

CN Iodonium, diphenyl-, salt with trifluoromethanesulfonic acid, compd. with 1,5-dichloro-1,1,3,3,5,5-hexamethyltrisiloxane polymer with 4,4'-thiobis[phenol] (1:1:?) (9CI) (CA INDEX NAME)



CM 1

CRN 329697-15-6

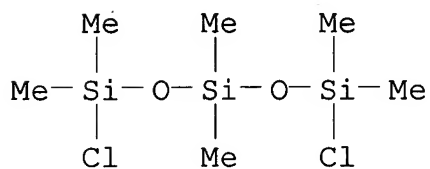
CMF (C12 H10 O2 S . C6 H18 Cl2 O2 Si3)x

CCI PMS

CM 2

CRN 3582-71-6

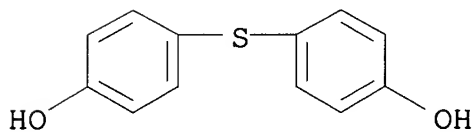
CMF C6 H18 Cl2 O2 Si3



CM 3

CRN 2664-63-3

CMF C12 H10 O2 S



CM 4

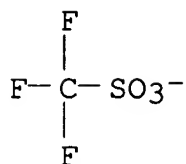
CRN 66003-76-7

CMF C12 H10 I . C F3 O3 S

CM 5

CRN 37181-39-8

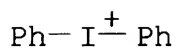
CMF C F3 O3 S



CM 6

CRN 10182-84-0

CMF C12 H10 I



RN 164580-22-7 HCAPLUS

CN Iodonium, diphenyl-, salt with trifluoromethanesulfonic acid, compd. with 1,4-cyclohexanediol polymer with 1,7-dichloro-1,1,3,3,5,5,7,7-octamethyltetrasiloxane and 4,4'-thiobis[phenol] (1:1:?) (9CI) (CA INDEX NAME)

CM 1

CRN 329695-82-1

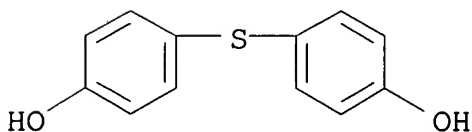
CMF (C12 H10 O2 S . C8 H24 Cl2 O3 Si4 . C6 H12 O2)x

CCI PMS

CM 2

CRN 2664-63-3

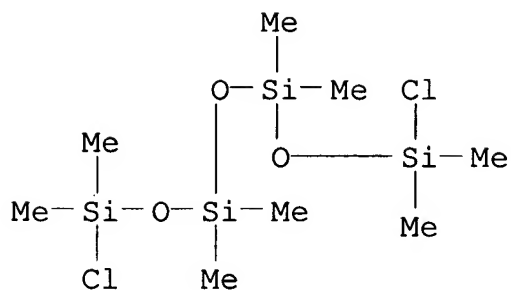
CMF C12 H10 O2 S



CM 3

CRN 2474-02-4

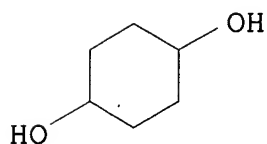
CMF C8 H24 Cl2 O3 Si4



CM 4

CRN 556-48-9

CMF C6 H12 O2



CM 5

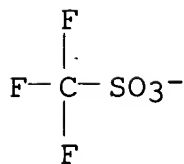
CRN 66003-76-7

CMF C12 H10 I . C F3 O3 S

CM 6

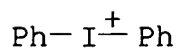
CRN 37181-39-8

CMF C F3 O3 S



CM 7

CRN 10182-84-0  
CMF C12 H10 I



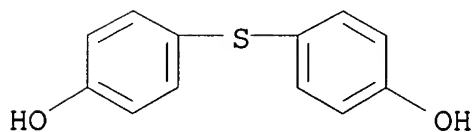
RN 164580-23-8 HCAPLUS  
CN Iodonium, diphenyl-, salt with trifluoromethanesulfonic acid,  
compd. with 1,4-benzenediol polymer with 1,7-dichloro-  
1,1,3,3,5,5,7,7-octamethyltetrasiloxane and 4,4'-thiobis[phenol]  
(1:1:?) (9CI) (CA INDEX NAME)

CM 1

CRN 329692-92-4  
CMF (C12 H10 O2 S . C8 H24 Cl2 O3 Si4 . C6 H6 O2)x  
CCI PMS

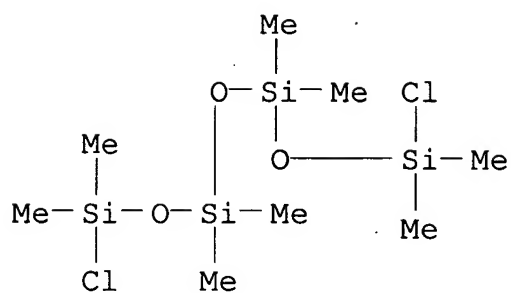
CM 2

CRN 2664-63-3  
CMF C12 H10 O2 S



CM 3

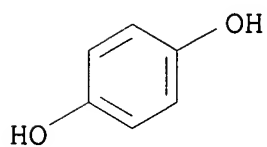
CRN 2474-02-4  
CMF C8 H24 Cl2 O3 Si4



CM 4

CRN 123-31-9

CMF C6 H6 O2



CM 5

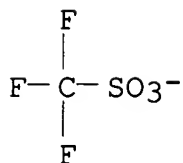
CRN 66003-76-7

CMF C12 H10 I . C F3 O3 S

CM 6

CRN 37181-39-8

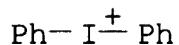
CMF C F3 O3 S



CM 7

CRN 10182-84-0

CMF C12 H10 I



RN 164580-24-9 HCAPLUS

CN Iodonium, diphenyl-, salt with trifluoromethanesulfonic acid, compd. with 1,7-dichloro-1,1,3,3,5,5,7,7-octamethyltetrasiloxane polymer with 4,4'-thiobis[phenol] (1:1:?) (9CI) (CA INDEX NAME)

CM 1

CRN 329697-16-7

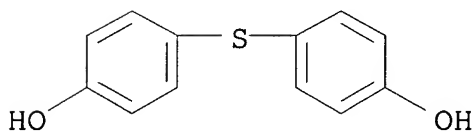
CMF (C12 H10 O2 S . C8 H24 Cl2 O3 Si4)x

CCI PMS

CM 2

CRN 2664-63-3

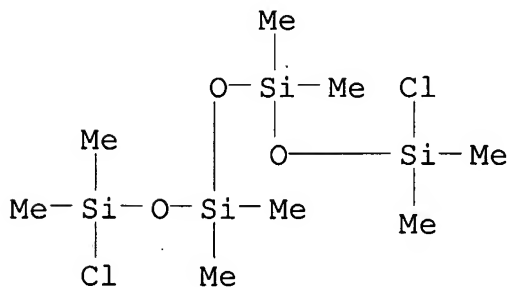
CMF C12 H10 O2 S



CM 3

CRN 2474-02-4

CMF C8 H24 Cl2 O3 Si4



CM 4

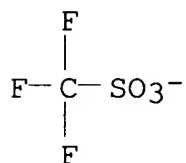
CRN 66003-76-7

CMF C12 H10 I . C F3 O3 S

CM 5

CRN 37181-39-8

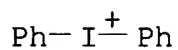
CMF C F3 O3 S



CM 6

CRN 10182-84-0

CMF C12 H10 I



RN 164580-26-1 HCAPLUS

CN Iodonium, diphenyl-, salt with trifluoromethanesulfonic acid, compd. with 1,4-cyclohexanedimethanol polymer with 1,7-dichloro-1,1,3,3,5,5,7,7-octamethyltetrasiloxane and 4,4'-thiobis[phenol] (1:1:?) (9CI) (CA INDEX NAME)

CM 1

CRN 329696-01-7

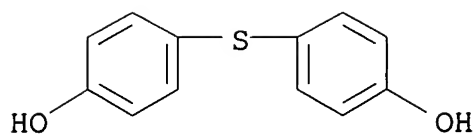
CMF (C12 H10 O2 S . C8 H24 C12 O3 Si4 . C8 H16 O2)x

CCI PMS

CM 2

CRN 2664-63-3

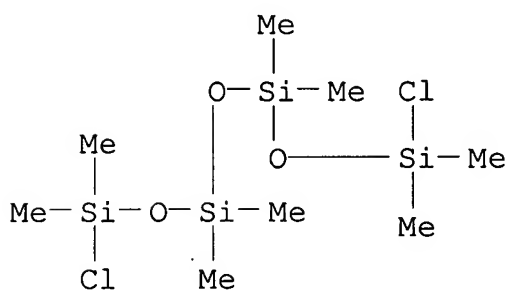
CMF C12 H10 O2 S



CM 3

CRN 2474-02-4

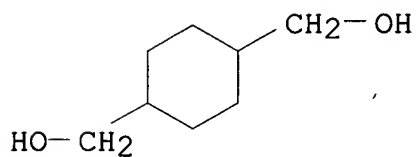
CMF C8 H24 Cl2 O3 Si4



CM 4

CRN 105-08-8

CMF C8 H16 O2



CM 5

CRN 66003-76-7

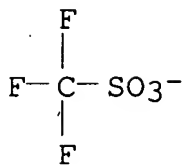
CMF Cl2 H10 I . C F3 O3 S

CM 6

CRN 37181-39-8

CMF C F3 O3 S

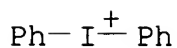




CM 7

CRN 10182-84-0

CMF C12 H10 I



RN 329321-82-6 HCAPLUS

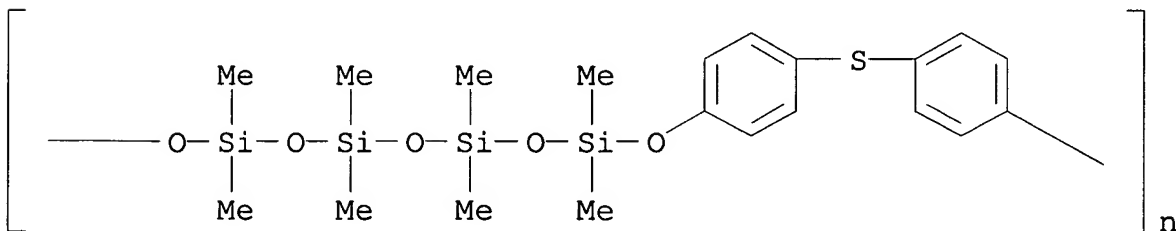
CN Iodonium, diphenyl-, salt with trifluoromethanesulfonic acid,  
 compd with poly[oxy(1,1,3,3,5,5,7,7-octamethyl-1,7-  
 tetrasiloxanediyloxy-1,4-phenylenethio-1,4-phenylene)] (1:1:?)  
 (9CI) (CA INDEX NAME)

CM 1

CRN 560127-41-5

CMF (C20 H32 O5 S Si4)n

CCI PMS



CM 2

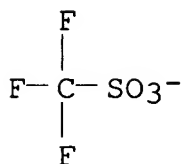
CRN 66003-76-7

CMF C12 H10 I . C F3 O3 S

CM 3

CRN 37181-39-8

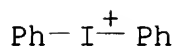
CMF C F3 O3 S



CM 4

CRN 10182-84-0

CMF C12 H10 I



RN 329321-85-9 HCAPLUS

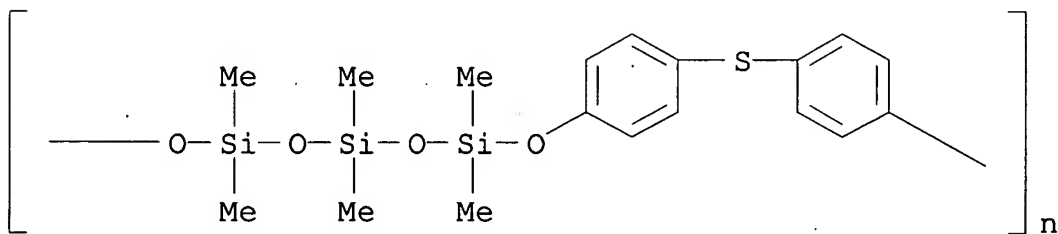
CN Iodonium, diphenyl-, salt with trifluoromethanesulfonic acid, compd. with poly[oxy(1,1,3,3,5,5-hexamethyl-1,5-trisiloxanediyl)oxy-1,4-phenylenethio-1,4-phenylene] (1:1:?) (9CI)  
(CA INDEX NAME)

CM 1

CRN 605665-94-9

CMF (C18 H26 O4 S Si3)n

CCI PMS

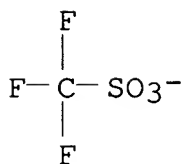


CM 2.

CRN 66003-76-7  
CMF C12 H10 I . C F3 O3 S

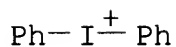
CM 3

CRN 37181-39-8  
CMF C F3 O3 S



CM 4

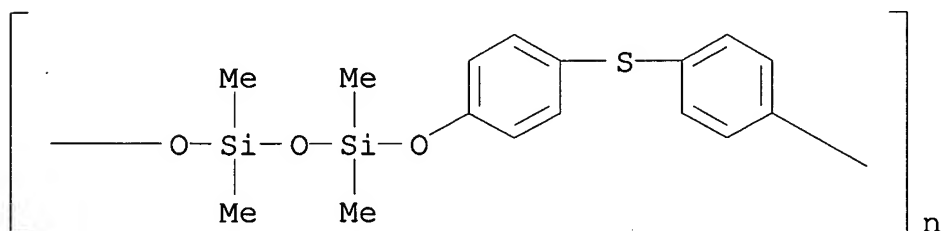
CRN 10182-84-0  
CMF C12 H10 I



RN 329322-05-6 HCAPLUS  
CN Iodonium, diphenyl-, salt with trifluoromethanesulfonic acid,  
compd with poly[oxy(1,1,3,3-tetramethyl-1,3-disiloxanediyl)oxy-1,4-  
phenylenethio-1,4-phenylene] (1:1:?) (9CI) (CA INDEX NAME)

CM 1

CRN 560124-63-2  
CMF (C16 H20 O3 S Si2)n  
CCI PMS



CM 2

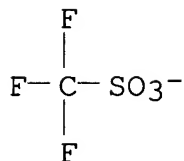
CRN 66003-76-7

CMF C12 H10 I . C F3 O3 S

CM 3

CRN 37181-39-8

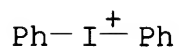
CMF C F3 O3 S



CM 4

CRN 10182-84-0

CMF C12 H10 I



RN 329322-16-9 HCAPLUS

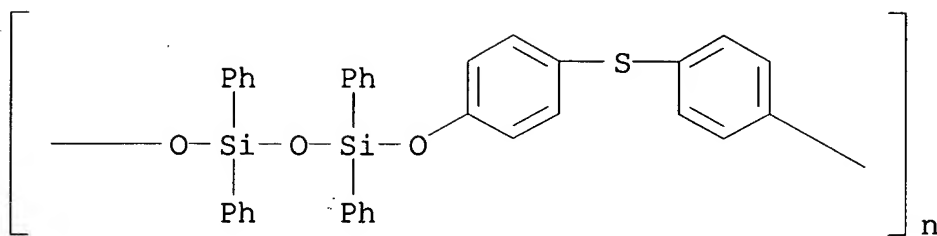
CN Iodonium, diphenyl-, salt with trifluoromethanesulfonic acid, compd with poly[oxy(1,1,3,3-tetraphenyl-1,3-disiloxanediyl)oxy-1,4-phenylenethio-1,4-phenylene] (1:1:?) (9CI) (CA INDEX NAME)

CM 1

CRN 560123-19-5

CMF (C36 H28 O3 S Si2)n

CCI PMS



CM 2

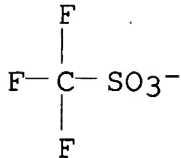
CRN 66003-76-7

CMF C12 H10 I . C F3 O3 S

CM 3

CRN 37181-39-8

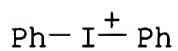
CMF C F3 O3 S



CM 4

CRN 10182-84-0

CMF C12 H10 I



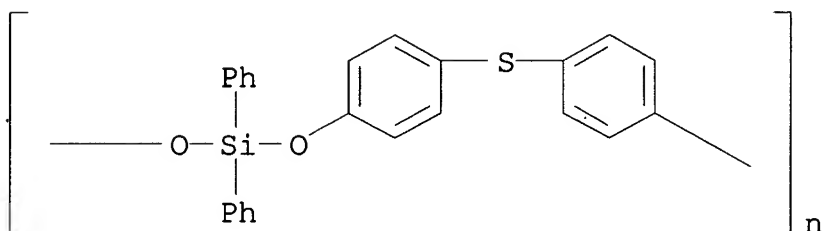
RN 329322-18-1 HCAPLUS

CN Iodonium, diphenyl-, salt with trifluoromethanesulfonic acid,  
 compd with poly[oxy(diphenylsilylene)oxy-1,4-phenylenethio-1,4-  
 phenylene] (1:1:?) (9CI) (CA INDEX NAME)

CM 1

CRN 560128-59-8

CMF (C24 H18 O2 S Si)n  
CCI PMS

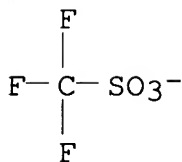


CM 2

CRN 66003-76-7  
CMF C12 H10 I . C F3 O3 S

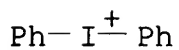
CM 3

CRN 37181-39-8  
CMF C F3 O3 S



CM 4

CRN 10182-84-0  
CMF C12 H10 I



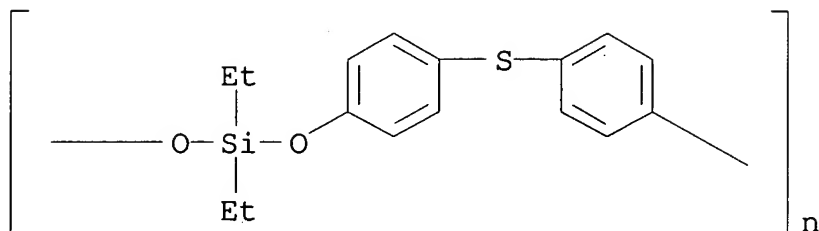
RN 329322-33-0 HCAPLUS  
CN Iodonium, diphenyl-, salt with trifluoromethanesulfonic acid,  
compd with poly[oxy(diethylsilylene)oxy-1,4-phenylenethio-1,4-  
phenylene] (1:1:?) (9CI) (CA INDEX NAME)

CM 1

CRN 560125-95-3

CMF (C16 H18 O2 S Si)n

CCI PMS



CM 2

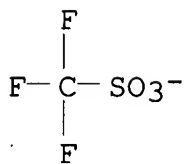
CRN 66003-76-7

CMF C12 H10 I . C F3 O3 S

CM 3

CRN 37181-39-8

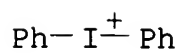
CMF C F3 O3 S



CM 4

CRN 10182-84-0

CMF C12 H10 I



IC ICM G03F007-004

ICS G03F007-031; G03F007-039; G03F007-075; H01L021-027

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 132852-30-3P **164580-15-8P 164580-22-7P**  
**164580-23-8P 164580-24-9P 164580-26-1P**  
**329321-82-6P 329321-85-9P 329322-05-6P**  
**329322-16-9P 329322-18-1P 329322-33-0P**

(photoresist compns. containing Si-containing polymer sulfonium salts as acid generators)

L27 ANSWER 7 OF 11 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1994:681382 HCAPLUS

DOCUMENT NUMBER: 121:281382

TITLE: Radiofrequency plasma polymerization of perfluoroionomer membrane materials

AUTHOR(S): Danilich, Michael J.; Gervasio, Dominic F.; Marchant, Roger E.

CORPORATE SOURCE: Dep. Macromol. Sci., Case Western Reserve Univ., Cleveland, OH, 44106, USA

SOURCE: Journal of Applied Polymer Science: Applied Polymer Symposium (1994), 54(Plasma Deposition of Polymeric Thin Films), 93-105  
CODEN: JPSSDD; ISSN: 0271-9460

DOCUMENT TYPE: Journal

LANGUAGE: English

AB Radiofrequency plasma polymerization was investigated as a method to prepare ionically conductive membrane materials for biomedical sensors. Plasma copolymers of chlorotrifluoroethylene (CTFE) and trifluoromethanesulfonic acid (TFMSA) exhibited ionic conductivity three

to four orders of magnitude higher than the water used to make the measurement, and gave ATR-FTIR and ESCA evidence for retained sulfonic acid groups. Plasma homopolymns. of CTFE and perfluoroallylphosphonic acid (PAPA) were investigated to determine suitable conditions for plasma copolymn. of the **two** monomers. Plasma homopolymd. CTFE had deposition rates varying from 4400 Å/h to 100 Å/h, was extremely hydrophobic, and showed spectroscopic evidence for a lightly branched, crosslinked fluorocarbon structure. Plasma homopolymd. PAPA deposited uniformly at approx. 780 Å/h, was extremely hydrophilic, and showed spectroscopic evidence for retained phosphonic acid groups. Plasma-polymerized PAPA had ionic conductivity **two** orders of magnitude higher than that of the water used to make the measurement. Increasing the discharge pressure from 30 mTorr to 100 mTorr resulted in decreased deposition rate for plasma homopolymd. CTFE and decreased monomer fragmentation in plasma-homopolymd. PAPA.

IT **121115-61-5P**



(properties of plasma-prepared membranes of)

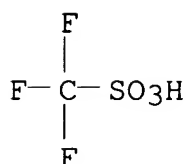
RN 121115-61-5 HCAPLUS

CN Methanesulfonic acid, trifluoro-, polymer with  
chlorotrifluoroethene (9CI) (CA INDEX NAME)

CM 1

CRN 1493-13-6

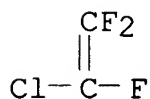
CMF C H F3 O3 S



CM 2

CRN 79-38-9

CMF C2 Cl F3

CC 35-7 (Chemistry of Synthetic High **Polymers**)

Section cross-reference(s): 38, 76

IT Contact angle

(of methylene **iodide** or water on fluoropolymer  
membranes)IT 75-11-6, Methylene **iodide** 7732-18-5, Water, uses  
(contact angle of methylene **iodide** or water on  
fluoropolymer membranes)

IT 9002-83-9P, Chlorotrifluoroethylene homopolymer

**121115-61-5P** 154075-47-5P

(properties of plasma-prepared membranes of)

L27 ANSWER 8 OF 11 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1988:130966 HCAPLUS

DOCUMENT NUMBER: 108:130966

TITLE: Copper-induced telomerization of  
tetrafluoroethylene with fluoroalkyl iodides

AUTHOR(S): Chen, Qingyun; Su, Debao; Yang, Zhenyu; Zhu,

CORPORATE SOURCE: Rongxian  
Shanghai Inst. Org. Chem., Acad. Sin.,  
Shanghai, Peop. Rep. China

SOURCE: Journal of Fluorine Chemistry (1987), 36(4),  
483-9  
CODEN: JFLCAR; ISSN: 0022-1139

DOCUMENT TYPE: Journal

LANGUAGE: English

OTHER SOURCE(S): CASREACT 108:130966

AB In the presence of catalytic amts. of copper, the telomerization  
of CF<sub>2</sub>:CF<sub>2</sub> with fluoroalkyl iodides, e.g., CF<sub>3</sub>CF<sub>2</sub>I and Cl(CF<sub>2</sub>)<sub>4</sub> I,  
was carried out at 80-100°. This is a much lower temperature  
range than usually required for telomerization  
(.apprx.200°). The reaction times in the catalytic  
procedure were also much shorter.

IT **66138-66-7P**  
(preparation of)

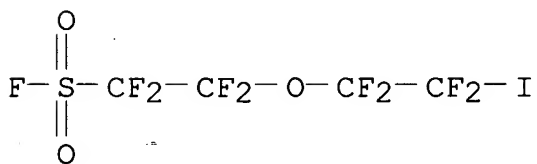
RN 66138-66-7 HCAPLUS

CN Ethanesulfonyl fluoride, 1,1,2,2-tetrafluoro-2-(1,1,2,2-  
tetrafluoro-2-iodoethoxy)-, telomer with tetrafluoroethene (9CI)  
(CA INDEX NAME)

CM 1

CRN 66137-74-4

CMF C4 F9 I O3 S



CM 2

CRN 9002-84-0

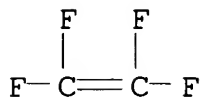
CMF (C2 F4)x

CCI PMS

CM 3

CRN 116-14-3

CMF C2 F4



CC 23-3 (Aliphatic Compounds)

IT 355-43-1P 423-39-2P 423-62-1P 507-63-1P 16486-97-8P  
 16486-98-9P 16486-99-0P 25398-32-7P **66138-66-7P**  
 67990-76-5P 67990-77-6P 68136-90-3P 113151-62-5P  
 113412-58-1P

(preparation of)

L27 ANSWER 9 OF 11 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1982:162080 HCAPLUS

DOCUMENT NUMBER: 96:162080

TITLE: Perfluoro- $\omega$ -iodo-3-oxaalkanesulfonyl  
 fluorides as intermediates for surfactants and  
 vinyl compounds

AUTHOR(S): Bargigia, G. A.; Caporiccio, G.; Pianca, M.

CORPORATE SOURCE: Cent. Ric. Sviluppo, Montedison Group, Milan,  
 20138, Italy

SOURCE: Journal of Fluorine Chemistry (1982), 19(3-6),  
 403-10

CODEN: JFLCAR; ISSN: 0022-1139

DOCUMENT TYPE: Journal

LANGUAGE: English

OTHER SOURCE(S): CASREACT 96:162080

AB FOCCF2SO2F quant. formed from SO3 and C2F4 through  
 tetrafluoroethanesultone, was converted into ICF2CF2OCF2CF2SO2F by  
 alkali fluoride, iodine and C2F4 in aprotic solvents. From the  
 iodo compound were derived C2F4 telomers having both fluorosulfonyl  
 and iodo terminal groups. These telomers were easily converted  
 into the surfactants CF3CF2(CF2CF2)nOCF2CF2SO3M (M = alkali) by  
 fluorination, and into the vinyl derivs.  
 CF2:CF(CF2CF2)nOCF2CF2SO2F by dehalogenation.

IT **66138-68-9P**

(preparation of)

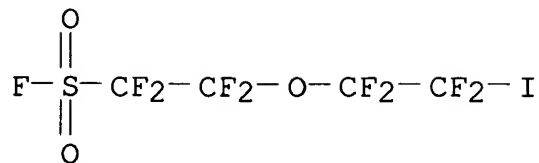
RN 66138-68-9 HCAPLUS

CN Ethanesulfonyl fluoride, 1,1,2,2-tetrafluoro-2-(1,1,2,2-  
 tetrafluoro-2-iodoethoxy)-, telomer with 1,1,2,3,3,3-hexafluoro-1-  
 propene and tetrafluoroethene (9CI) (CA INDEX NAME)

CM 1

CRN 66137-74-4

CMF C4 F9 I O3 S



CM 2

CRN 25067-11-2

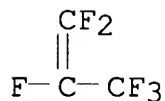
CMF (C3 F6 . C2 F4)x

CCI PMS

CM 3

CRN 116-15-4

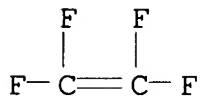
CMF C3 F6



CM 4

CRN 116-14-3

CMF C2 F4



IT **66138-68-9DP**, fluorination and dehalogenation products  
(preparation of, as surfactant)

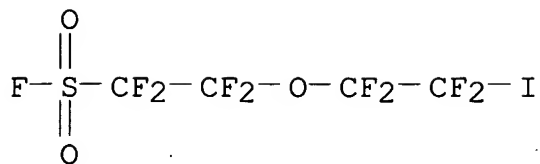
RN 66138-68-9 HCAPLUS

CN Ethanesulfonyl fluoride, 1,1,2,2-tetrafluoro-2-(1,1,2,2-tetrafluoro-2-iodoethoxy)-, telomer with 1,1,2,3,3,3-hexafluoro-1-propene and tetrafluoroethene (9CI) (CA INDEX NAME)

CM 1

CRN 66137-74-4

CMF C4 F9 I O3 S



CM 2

CRN 25067-11-2

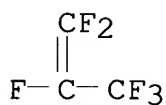
CMF (C3 F6 . C2 F4)x

CCI PMS

CM 3

CRN 116-15-4

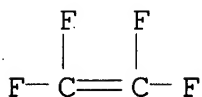
CMF C3 F6



CM 4

CRN 116-14-3

CMF C2 F4



CC 23-12 (Aliphatic Compounds)

IT 677-67-8P 697-18-7P 66137-74-4P **66138-68-9P**

67990-76-5P 81439-24-9P

(preparation of)

IT **66138-68-9DP**, fluorination and dehalogenation products  
(preparation of, as surfactant)

DOCUMENT NUMBER: 91:92454  
 TITLE: Improved fluorocarbon cation-exchange membrane  
 INVENTOR(S): Asawa, Tatsuro; Miyake, Haruhisa; Kanke, Yoshio  
 PATENT ASSIGNEE(S): Asahi Glass Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 4 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 54052690	A2	19790425	JP 1977-118597	1977 1004
JP 60026145	B4	19850621	JP 1977-118597	A 1977 1004

PRIORITY APPLN. INFO.:

AB The title mech.-stable membranes are crosslinked copolymers of  $I(CF_2)_pO(CF_2CF_2O)_q[CF(CF_3)CF_2O]_rCF:CF_2$  ( $p = 2-9$ ;  $q, r = 0-5$ ),  $CF_2:CZZ1(Z, Z1 = F, Cl, H, \text{ or } CF_3)$ , and  $CF_2:CX(CF_2CFY)_lOm(CFY)_nA$  ( $X = F \text{ or } CF_3$ ;  $Y, Y1 = F \text{ or } Cl-10$  perfluoroalkyl;  $A = SO_3H, COOH, PO_2H_2, \text{ hydroxyaryl, } C(CF_3)_2OH, \text{ or their precursors}$ ;  $l = 0-3$ ;  $m = 0 \text{ or } 1$ ;  $n = 0-12$ ); the copolymers are comprised of 0.1-10 and 1-50 mol% of the 1st and last monomers, resp. Thus, heating  $I(CF_2)_4OCF:CF_2$  (I) 6.3,  $CF_2:CFOCF_2CF(CF_3)OCF_2CF_2SO_2F$  37.5., trichlorotrifluoromethane 31.5, and azobisisobutyronitrile 0.14 g under N in a stainless steel autoclave at  $70^\circ$ , and pressuring with  $C_2F_4$  at 10.5 kg/cm<sup>2</sup> for 20 h gave a copolymer containing 2.6 mol% I. The copolymer (6.2 g) was pressed at  $200^\circ$  to give a 200 $\mu$ -thick film, heated at  $250^\circ$  for 6 h in vacuo to remove I and crosslink, and hydrolyzed. The 25 cm<sup>2</sup> membrane of exchange capacity 0.79 mequiv/g was used at  $85^\circ$  and c.d. 20 A/dm<sup>2</sup> to electrolyze a feed of 4N NaCl (150 mL/h) and water to give 8N NaOH with current efficiency 70%. The dimensional change of the membrane was 0.7% after 3 mo as compared with 4.5 for a membrane prepared without I.

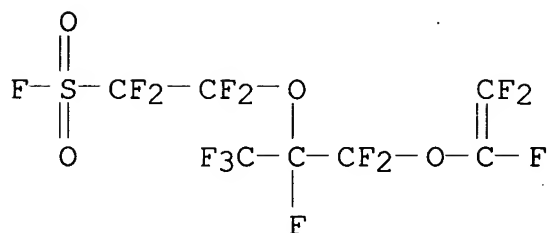
IT **71132-02-0D**, crosslinked and hydrolyzed  
 (membranes, dimensionally-stable, for electrolysis of brines)  
 RN 71132-02-0 HCAPLUS  
 CN Ethanesulfonyl fluoride, 2-[1-[difluoro[(trifluoroethenyl)oxy]methyl]-1,2,2,2-tetrafluoroethoxy]-1,1,2,2-tetrafluoro-, polymer with 1,1,2,2,3,3,4,4-octafluoro-1-iodo-4-[(trifluoroethenyl)oxy]butane

and tetrafluoroethene (9CI) (CA INDEX NAME)

CM 1

CRN 16090-14-5

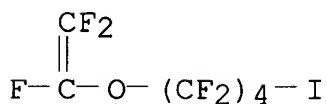
CMF C7 F14 O4 S



CM 2

CRN 15498-33-6

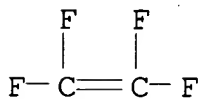
CMF C6 F11 I O



CM 3

CRN 116-14-3

CMF C2 F4



IC C08J005-22

CC 36-3 (Plastics Manufacture and Processing)

IT **71132-02-0D**, crosslinked and hydrolyzed  
(membranes, dimensionally-stable, for electrolysis of brines)

L27 ANSWER 11 OF 11 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1978:153252 HCAPLUS

DOCUMENT NUMBER: 88:153252  
 TITLE: Fluorooxaalkanesulfonic acids and their derivatives  
 INVENTOR(S): Caporiccio, Gerardo; Bargigia, Gianangelo; Guidetti, Giampiero  
 PATENT ASSIGNEE(S): Montedison S.p.A., Italy  
 SOURCE: Ger. Offen., 38 pp.  
 CODEN: GWXXBX  
 DOCUMENT TYPE: Patent  
 LANGUAGE: German  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
DE 2735210	A1	19780209	DE 1977-2735210	1977 0804
DE 2735210 DK 7703437	C2 A	19910103 19780207	DK 1977-3437	1977 0801
NO 7702722	A	19780207	NO 1977-2722	1977 0801
NO 145235 NO 145235 SE 7708780	B C A	19811102 19820210 19780207	SE 1977-8780	1977 0801
NL 7708480	A	19780208	NL 1977-8480	1977 0801
NL 187439 NL 187439 AU 7727582	B C A1	19910501 19911001 19790208	AU 1977-27582	1977 0803
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NL 9100799	A	19911101	NL 1991-799	1991
				0508
NL 189913	B	19930401		
NL 189913	C	19930901		
PRIORITY APPLN. INFO.:			IT 1976-26116	A
				1976
				0806
			IT 1977-20831	A
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				0302
			IT 1976-20831	A
				1977
				0302

NL 1977-8480

A3

1977

0801

US 1977-821394

A3

1977

0803

AB FSO<sub>2</sub>CF<sub>2</sub>COF [677-67-8] was treated with KF to prepare FSO<sub>2</sub>CF<sub>2</sub>CF<sub>2</sub>OK which was treated with iodine and F<sub>2</sub>C:CF<sub>2</sub> [116-14-3] to prepare FSO<sub>2</sub>CF<sub>2</sub>CF<sub>2</sub>OCF<sub>2</sub>CF<sub>2</sub>I (I) [66137-74-4]. I was used with F<sub>2</sub>C:CF<sub>2</sub> and/or F<sub>2</sub>C:CF<sub>2</sub>CF<sub>3</sub> to prepare telomers. The telomers were treated with NaF or ClSO<sub>3</sub>H to replace iodine with F or SO<sub>3</sub>H, giving surfactants which were useful in electroplating baths or in pickling compns. for steel. The telomers were also dehydroiodinated with EtMgBr to give α-olefins (containing a terminal FSO<sub>2</sub>CF<sub>2</sub>CF<sub>2</sub>O group) which were copolymd. with F<sub>2</sub>C:CF<sub>2</sub>, F<sub>2</sub>C:CF<sub>2</sub>CF<sub>3</sub>, and/or F<sub>2</sub>C:CH<sub>2</sub>, e.g. to give elastomers having good resistance to heat and chems. after vulcanization.

IT **66138-66-7P 66138-67-8P 66138-68-9P**

(preparation and reactions of)

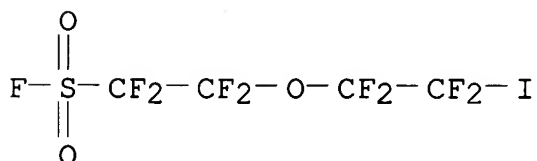
RN 66138-66-7 HCAPLUS

CN Ethanesulfonyl fluoride, 1,1,2,2-tetrafluoro-2-(1,1,2,2-tetrafluoro-2-iodoethoxy)-, telomer with tetrafluoroethene (9CI)  
(CA INDEX NAME)

CM 1

CRN 66137-74-4

CMF C4 F9 I O3 S



CM 2

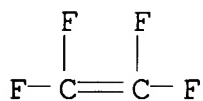
CRN 9002-84-0

CMF (C2 F4)x

CCI PMS

CM 3

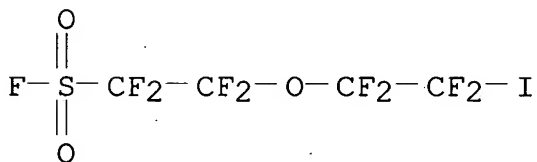
CRN 116-14-3  
CMF C2 F4



RN 66138-67-8 HCAPLUS  
CN Ethanesulfonyl fluoride, 1,1,2,2-tetrafluoro-2-(1,1,2,2-tetrafluoro-2-iodoethoxy)-, telomer with 1,1,2,3,3,3-hexafluoro-1-propene (9CI) (CA INDEX NAME)

CM 1

CRN 66137-74-4  
CMF C4 F9 I O3 S

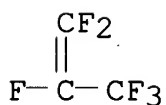


CM 2

CRN 25120-07-4  
CMF (C3 F6)x  
CCI PMS

CM 3

CRN 116-15-4  
CMF C3 F6



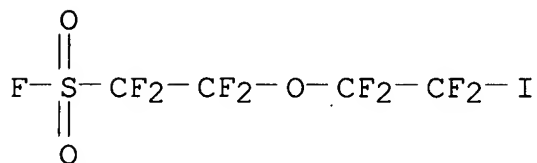
RN 66138-68-9 HCAPLUS  
CN Ethanesulfonyl fluoride, 1,1,2,2-tetrafluoro-2-(1,1,2,2-tetrafluoro-2-iodoethoxy)-, telomer with 1,1,2,3,3,3-hexafluoro-1-

propene and tetrafluoroethene (9CI) (CA INDEX NAME)

CM 1

CRN 66137-74-4

CMF C4 F9 I O3 S



CM 2

CRN 25067-11-2

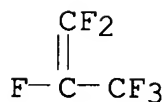
CMF (C3 F6 . C2 F4)x

CCI PMS

CM 3

CRN 116-15-4

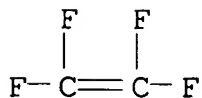
CMF C3 F6



CM 4

CRN 116-14-3

CMF C2 F4



IC C07C143-70

CC 35-3 (Synthetic High Polymers)

Section cross-reference(s): 23, 46

IT 66137-74-4P **66138-66-7P 66138-67-8P**  
**66138-68-9P**  
(preparation and reactions of)